

09966689 · 0982701

FIG. 1A

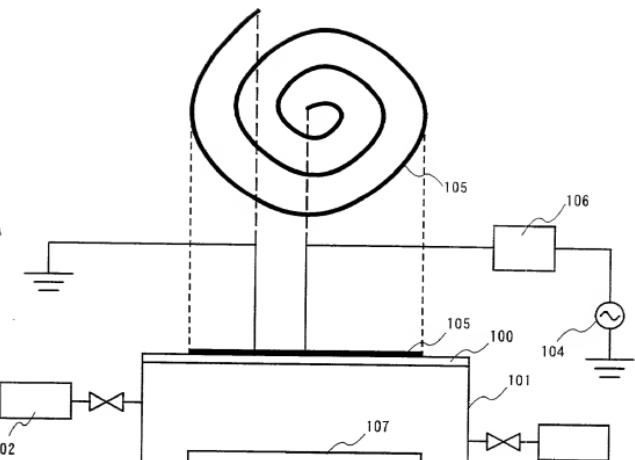


FIG. 1B

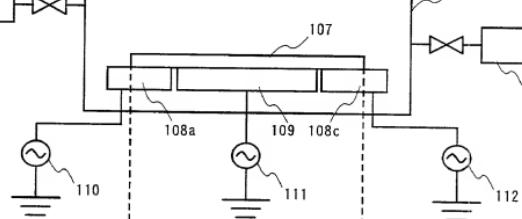


FIG. 1C

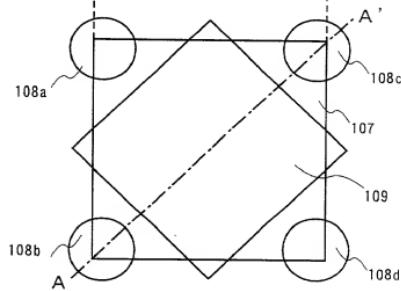


FIG. 2A

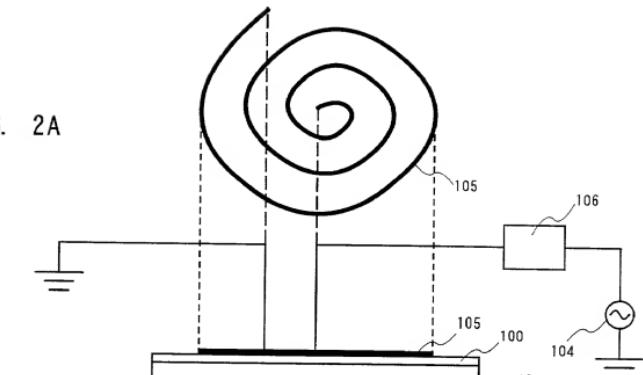


FIG. 2B

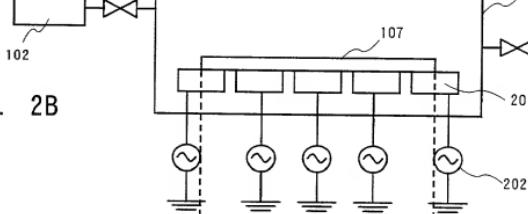
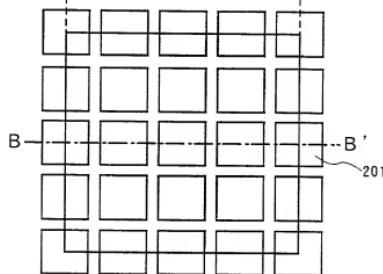


FIG. 2C



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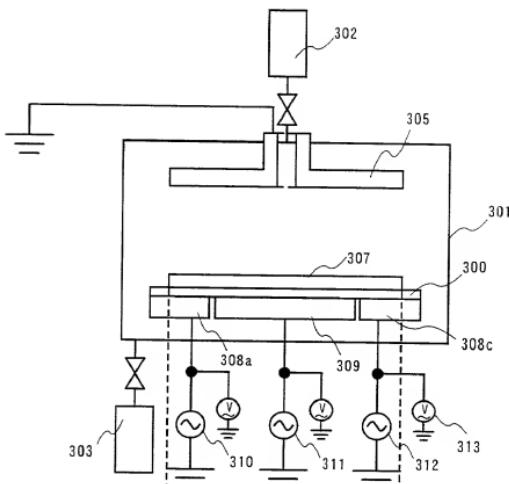


FIG. 3A

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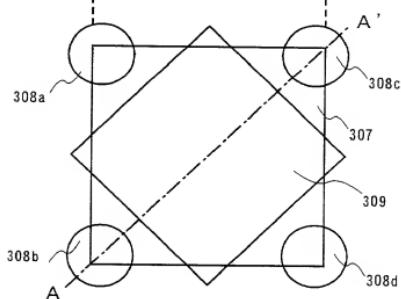


FIG. 3B

FIG. 260: 68999660

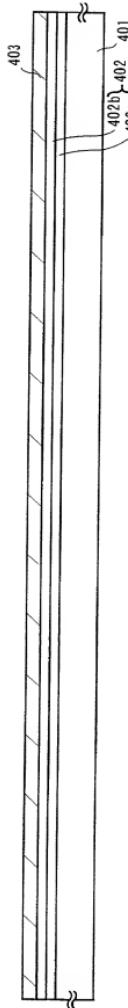


FIG. 4A

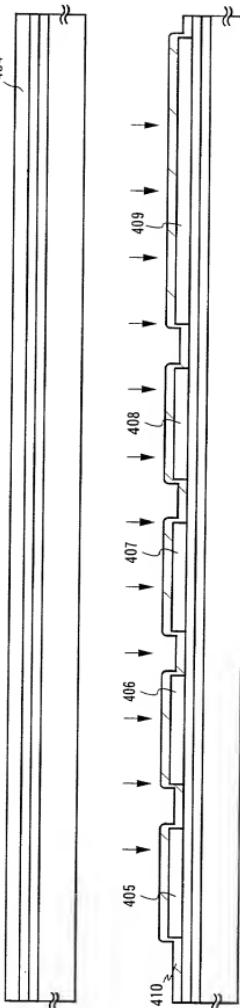


FIG. 4B

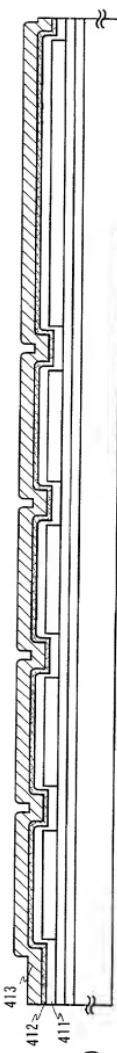


FIG. 4C

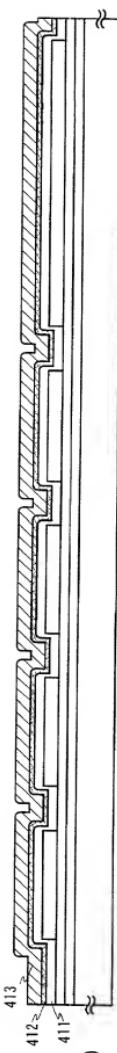


FIG. 4D

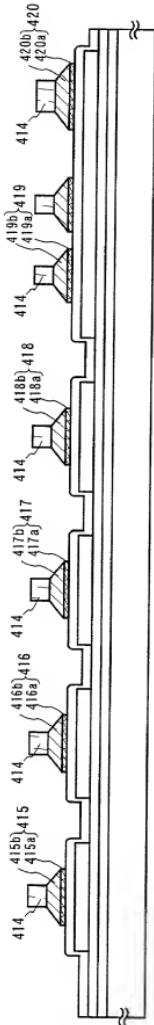


FIG. 5A

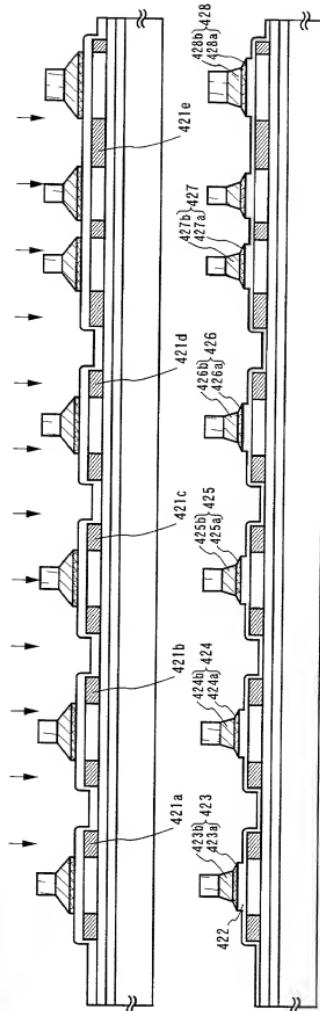


FIG. 5B

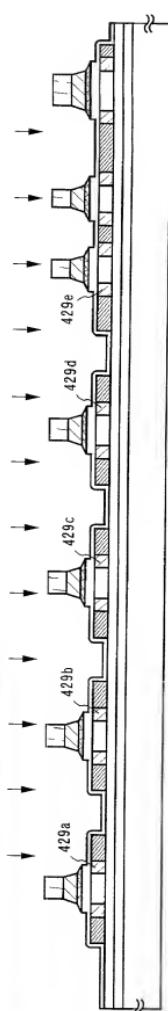
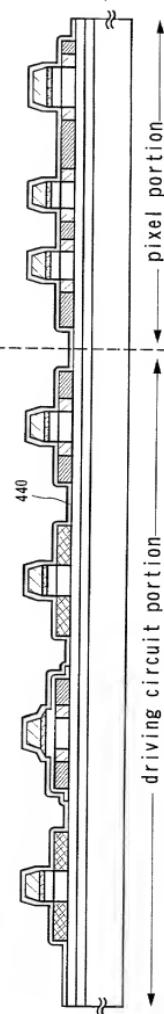
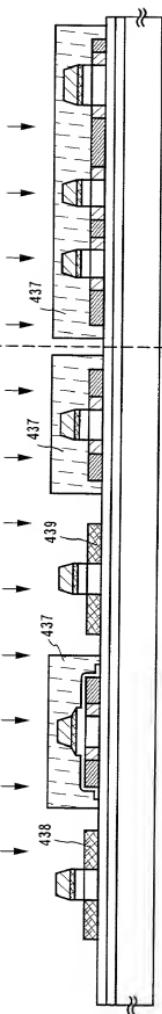
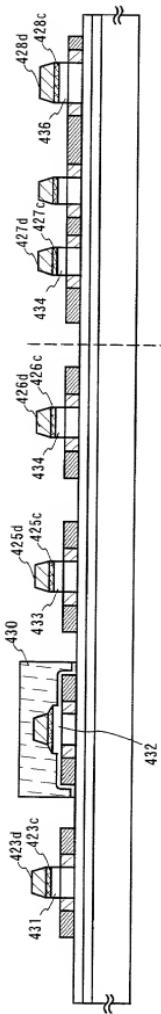


FIG. 5C



FIG. 5D



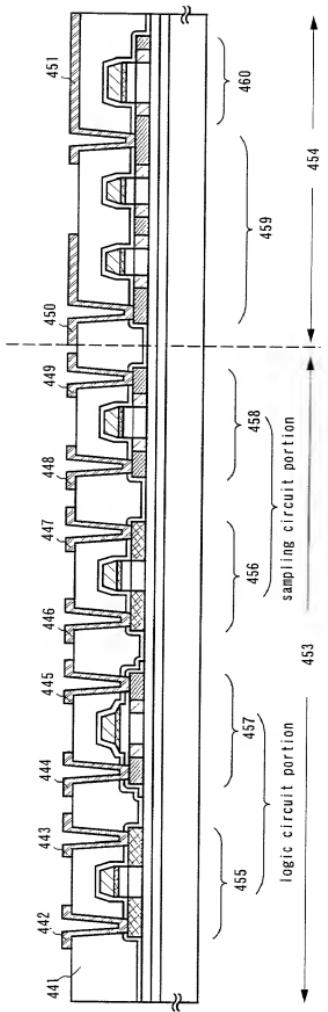


FIG. 7

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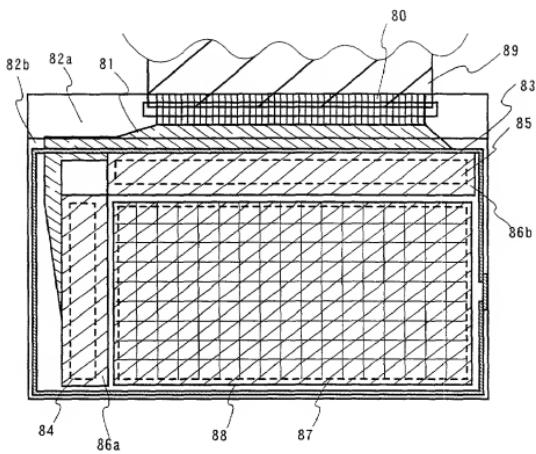


FIG. 8

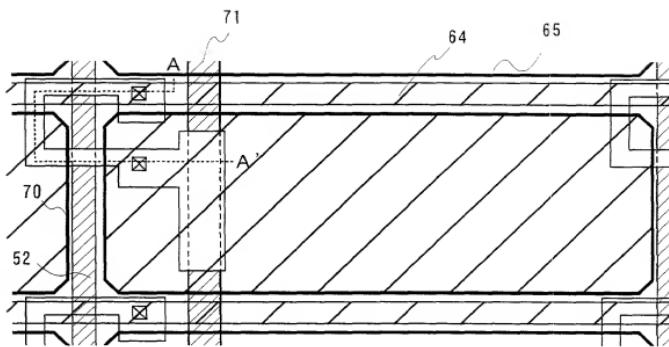


FIG. 9A

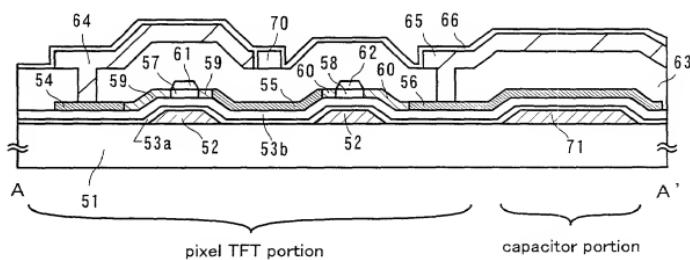


FIG. 9B

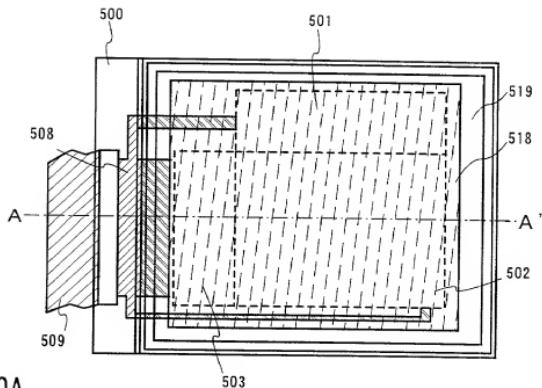


FIG. 10A

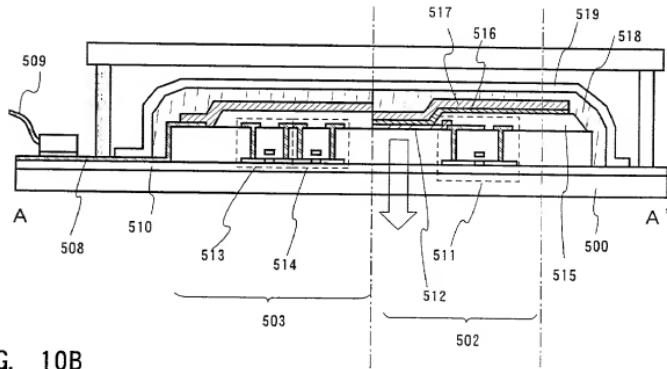


FIG. 10B

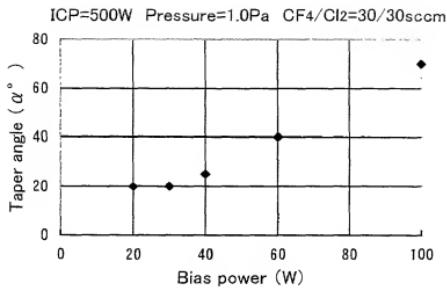


FIG. 11 Dependence of taper angle on bias power.

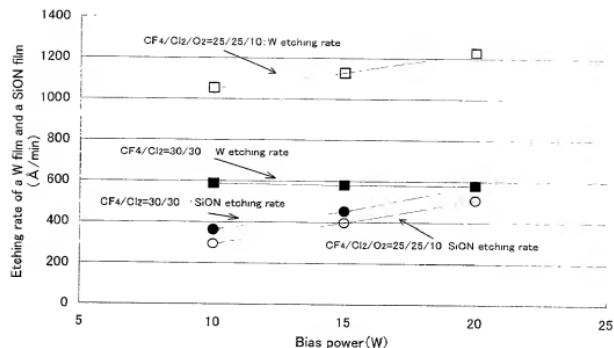


FIG. 12  
Dependence of an etching rate of a W film and an SiON film on bias power.

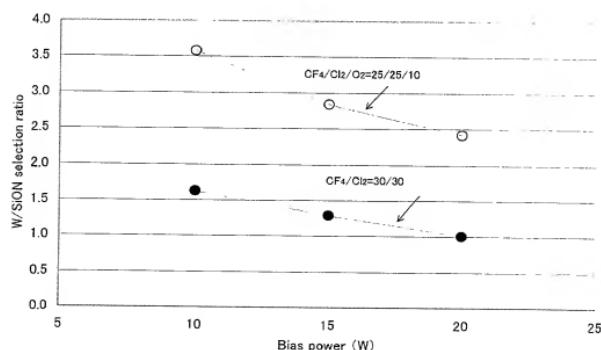


FIG. 13  
Dependence of a selection ratio between a W film and an SiON film on a bias power.

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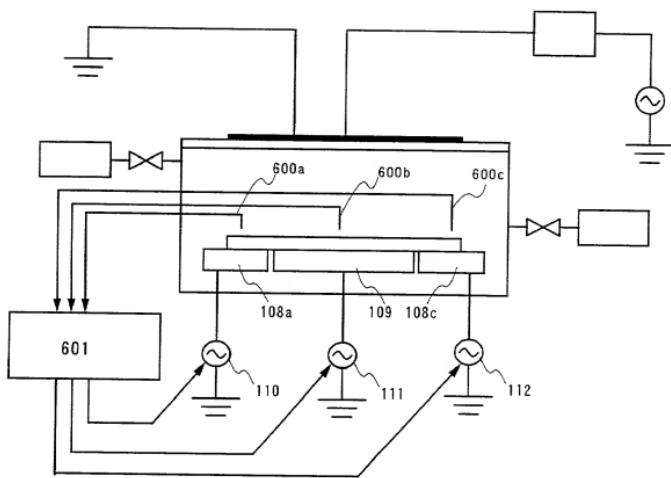


FIG. 14

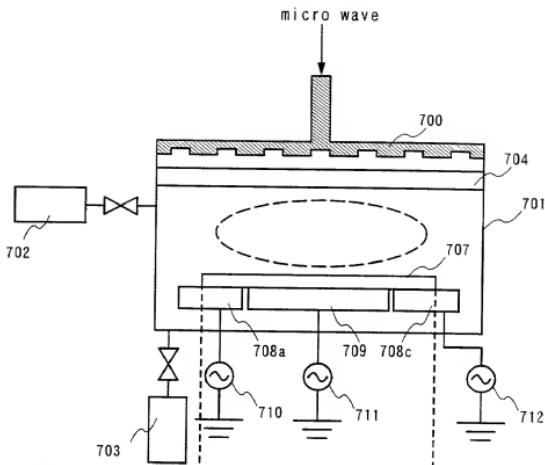


FIG. 15A

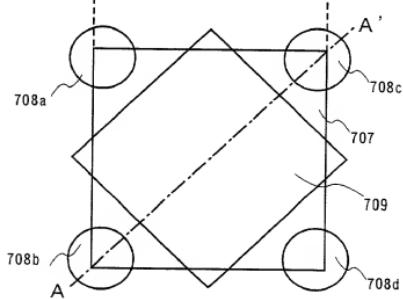


FIG. 15B

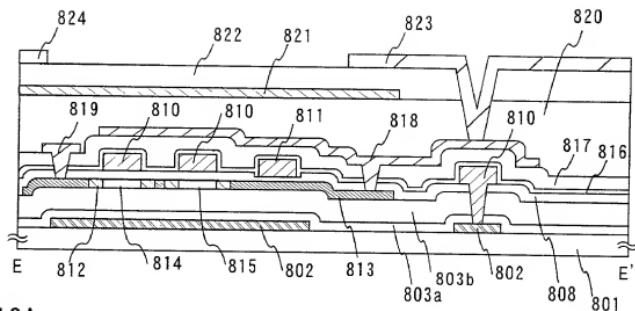


FIG. 16A

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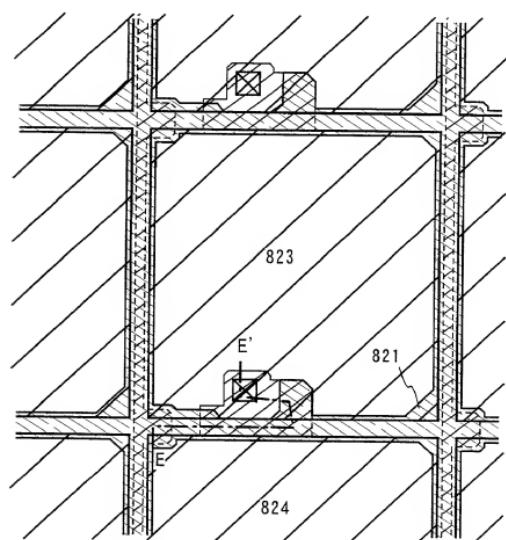


FIG. 16B

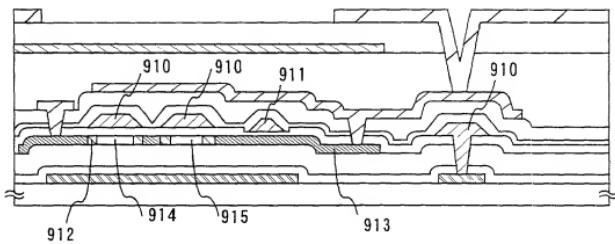


FIG. 17

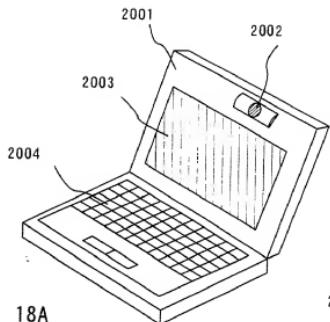


FIG. 18A

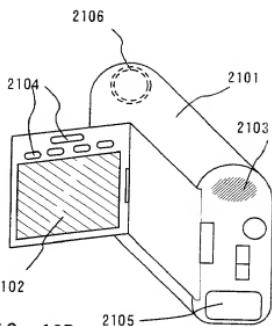


FIG. 18B

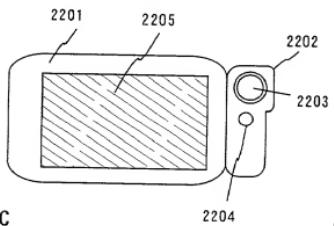


FIG. 18C

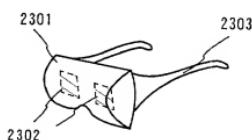


FIG. 18D

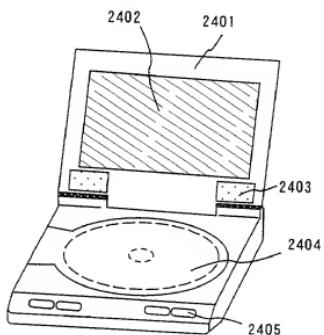


FIG. 18E

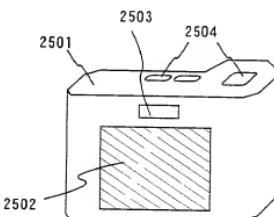


FIG. 18F

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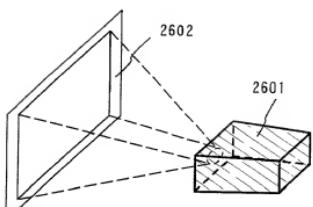


FIG. 19A

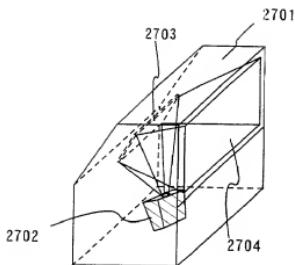


FIG. 19B

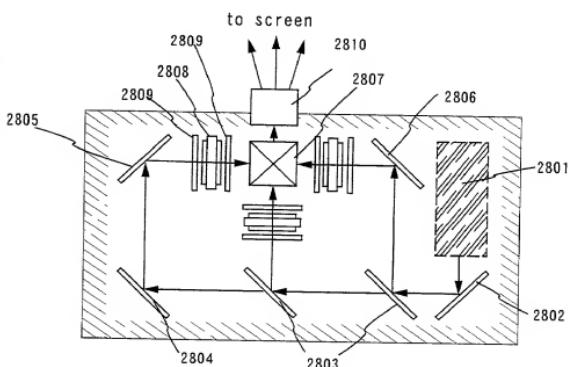


FIG. 19C

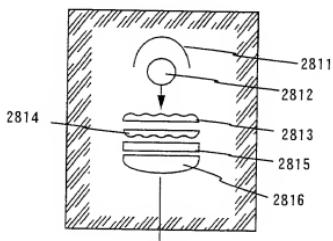


FIG. 19D

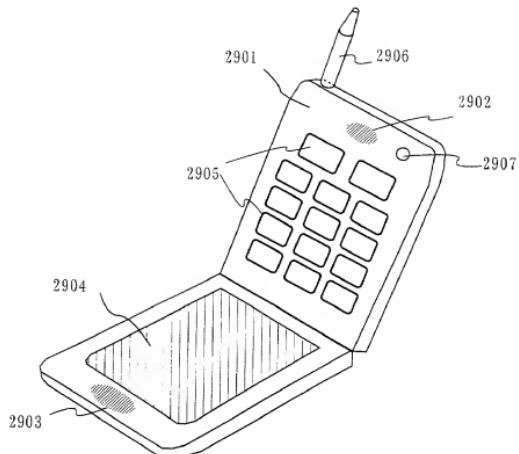


FIG. 20A

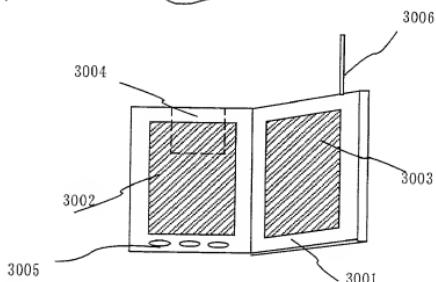


FIG. 20B

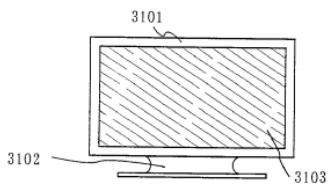


FIG. 20C

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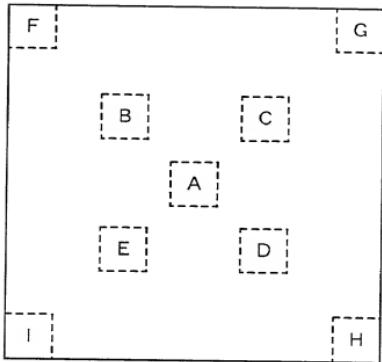


FIG. 21A

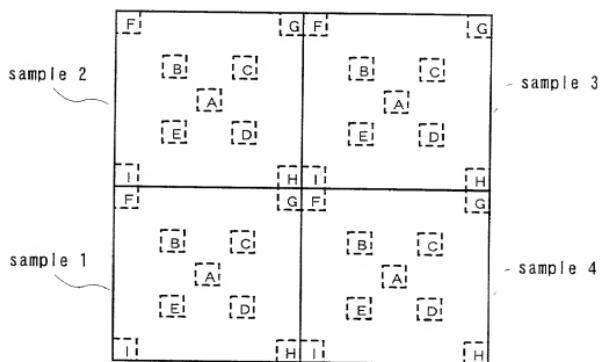


FIG. 21B